

09681304\_CLSTITLES

Titles of Most Frequently Occurring Classifications of Patents Returned

From A Search of 09681304 on March 13, 2002

12	438/52	(3 OR, 9 XR)
	Class 438 :	SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS
	438/48	MAKING DEVICE OR CIRCUIT RESPONSIVE TO NONELECTRICAL SIGNAL
	438/50	.Physical stress responsive
	438/52	..Having cantilever element
11	310/307	(10 OR, 1 XR)
	Class 310 :	ELECTRICAL GENERATOR OR MOTOR STRUCTURE
	310/300	NON-DYNAMOELECTRIC
	310/306	.Thermal or pyromagnetic
	310/307	..With heat actuated bimetal element
10	438/50	(4 OR, 6 XR)
	Class 438 :	SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS
	438/48	MAKING DEVICE OR CIRCUIT RESPONSIVE TO NONELECTRICAL SIGNAL
	438/50	.Physical stress responsive
9	216/2	(4 OR, 5 XR)
	Class 216 :	ETCHING A SUBSTRATE: PROCESSES
	216/2	ETCHING OF SEMICONDUCTOR MATERIAL TO PRODUCE A
N		ARTICLE HAVING A NONELECTRICAL FUNCTION
9	257/417	(2 OR, 7 XR)
	Class 257 :	ACTIVE SOLID-STATE DEVICES
	257/414	RESPONSIVE TO NON-ELECTRICAL SIGNAL (E.G., CHEMICAL, STRESS, LIGHT, OR MAGNETIC FIELD
D SENSORS)		
	257/415	.Physical deformation
	257/417	..Strain sensors
7	310/40MM	(3 OR, 4 XR)
	Class 310 :	ELECTRICAL GENERATOR OR MOTOR STRUCTURE
	310/10	DYNAMOELECTRIC
	310/40R	.Rotary
	310/40MM	..Miniature motors
6	257/415	(3 OR, 3 XR)
	Class 257 :	ACTIVE SOLID-STATE DEVICES

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257/414 RESPONSIVE TO NON-ELECTRICAL SIGNAL (E.G.,  
CHEMICAL, STRESS, LIGHT, OR MAGNETIC FIELD  
SENSORS)

257/415 .Physical deformation

6 438/455 (1 OR, 5 XR)  
Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/455 BONDING OF PLURAL SEMICONDUCTOR SUBSTRATES

5 156/345 (2 OR, 3 XR)  
Class 156 : ADHESIVE BONDING AND MISCELLANEOUS CHEMICAL  
MANUFACTURE

156/345 DIFFERENTIAL ETCHING APPARATUS

4 73/514.36 (0 OR, 4 XR)  
Class 073 : MEASURING AND TESTING

73/488 SPEED, VELOCITY, OR ACCELERATION

73/514.01 .Acceleration determination utilizing inertial  
element

73/514.36 ..Pendulum or beam

4 118/723IR (2 OR, 2 XR)  
Class 118 : COATING APPARATUS

118/715 GAS OR VAPOR DEPOSITION

118/722 .With treating means (e.g., jarring)

118/723R ..By creating electric field (e.g., gas  
activation, plasma, etc.)

118/723I ...Radio frequency antenna or radio frequency  
inductive coil discharge means

118/723IR ....Producing energized gas remotely located  
from substrate

4 118/728 (0 OR, 4 XR)  
Class 118 : COATING APPARATUS

118/715 GAS OR VAPOR DEPOSITION

118/728 .Work support

4 257/254 (1 OR, 3 XR)  
Class 257 : ACTIVE SOLID-STATE DEVICES

257/213 FIELD EFFECT DEVICE

257/252 .Responsive to non-optical, non-electrical  
signal

257/254 ..Physical deformation (e.g., strain sensor,  
acoustic wave detector)

4 310/306 (1 OR, 3 XR)  
Class 310 : ELECTRICAL GENERATOR OR MOTOR STRUCTURE

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310/300 NON-DYNAMOELECTRIC

310/306 .Thermal or pyromagnetic

4 438/460 (3 OR, 1 XR)

Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/460 SEMICONDUCTOR SUBSTRATE DICING

4 438/526 (1 OR, 3 XR)

Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/510 INTRODUCTION OF CONDUCTIVITY MODIFYING DOPANT  
INTO SEMICONDUCTIVE MATERIAL

438/514 .Ion implantation of dopant into semiconductor  
region

438/526 ..Forming buried region

4 438/53 (1 OR, 3 XR)

Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/48 MAKING DEVICE OR CIRCUIT RESPONSIVE TO  
NONELECTRICAL SIGNAL

438/50 .Physical stress responsive

438/53 ..Having diaphragm element

3 73/514.21 (2 OR, 1 XR)

Class 073 : MEASURING AND TESTING

73/488 SPEED, VELOCITY, OR ACCELERATION

73/514.01 .Acceleration determination utilizing inertial  
element

73/514.16 ..Specific type of electric sensor or specific  
type of magnetic sensor

73/514.17 ...Rebalance

73/514.21 ....Pendulum or beam

3 118/723E (2 OR, 1 XR)

Class 118 : COATING APPARATUS

118/715 GAS OR VAPOR DEPOSITION

118/722 .With treating means (e.g., jarring)

118/723R ..By creating electric field (e.g., gas  
activation, plasma, etc.)

118/723E ...Having glow discharge electrodes (e.g., DC,  
AC, RF, etc.)

3 118/723I (0 OR, 3 XR)

Class 118 : COATING APPARATUS

118/715 GAS OR VAPOR DEPOSITION

118/722 .With treating means (e.g., jarring)

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- 118/723R ..By creating electric field (e.g., gas activation, plasma, etc.)
- 118/723I ...Radio frequency antenna or radio frequency inductive coil discharge means
- 3 118/723MP (0 OR, 3 XR)  
 Class 118 : COATING APPARATUS  
 118/715 GAS OR VAPOR DEPOSITION  
 118/722 .With treating means (e.g., jarring)  
 118/723R ..By creating electric field (e.g., gas activation, plasma, etc.)  
 118/723MP ...Multiple gas energizing means associated with one deposition site (i.e., excluding s  
 ubstrate heater as an energizing means)
- 3 118/733 (0 OR, 3 XR)  
 Class 118 : COATING APPARATUS  
 118/715 GAS OR VAPOR DEPOSITION  
 118/733 .Chamber seal
- 3 148/33.2 (3 OR, 0 XR)  
 Class 148 : METAL TREATMENT  
 148/33 BARRIER LAYER STOCK MATERIAL, P-N TYPE  
 148/33.2 .With recess, void, dislocation, grain boundaries or channel openings
- 3 156/247 (0 OR, 3 XR)  
 Class 156 : ADHESIVE BONDING AND MISCELLANEOUS CHEMICAL MANUFACTURE  
 156/1 METHODS  
 156/60 .Surface bonding and/or assembly therefor  
 156/247 ..With stripping of adhered lamina
- 3 156/267 (0 OR, 3 XR)  
 Class 156 : ADHESIVE BONDING AND MISCELLANEOUS CHEMICAL MANUFACTURE  
 156/1 METHODS  
 156/60 .Surface bonding and/or assembly therefor  
 156/250 ..With cutting, punching, tearing or severing  
 156/267 ...Flash, trim or excess removal
- 3 200/181 (2 OR, 1 XR)  
 Class 200 : ELECTRICITY: CIRCUIT MAKERS AND BREAKERS  
 200/181 ELECTROSTRICTIVE OR ELECTROSTATIC
- 3 204/298.15 (1 OR, 2 XR)

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Class 204 : CHEMISTRY: ELECTRICAL AND WAVE ENERGY
204/193 APPARATUS
204/298.01 .Coating, forming or etching by sputtering
204/298.02 ..Coating
204/298.15 ...Specified work holder

3 216/67 (0 OR, 3 XR)
Class 216 : ETCHING A SUBSTRATE: PROCESSES
216/58 GAS PHASE ETCHING OF SUBSTRATE
216/63 .Application of energy to the gaseous etchant
        or to the substrate being etched
216/67 ..Using plasma

3 271/194 (2 OR, 1 XR)
Class 271 : SHEET FEEDING OR DELIVERING
271/278 DELIVERING
271/194 .By pneumatic conveyor

3 271/195 (0 OR, 3 XR)
Class 271 : SHEET FEEDING OR DELIVERING
271/278 DELIVERING
271/194 .By pneumatic conveyor
271/195 ..Using pressurized gas

3 310/309 (2 OR, 1 XR)
Class 310 : ELECTRICAL GENERATOR OR MOTOR STRUCTURE
310/300 NON-DYNAMOELECTRIC
310/308 .Charge accumulating
310/309 ..Electrostatic

3 310/DIG 6 (0 OR, 3 XR)
Class 310 : ELECTRICAL GENERATOR OR MOTOR STRUCTURE
310/DIG 6 Printed-circuit motors and components

3 359/224 (1 OR, 2 XR)
Class 359 : OPTICS: SYSTEMS
359/196 DEFLECTION USING A MOVING ELEMENT OR MEDIUM
        (OFFSETTING OR CHANGING AT LEAST A PORTIO
N OF THE BEAM)
359/223 .By moving a reflective element
359/224 ..Reflective element moved by deformable
        support

3 359/230 (0 OR, 3 XR)
Class 359 : OPTICS: SYSTEMS
359/227 LIGHT CONTROL BY OPAQUE ELEMENT OR MEDIUM
        MOVABLE IN OR THROUGH LIGHT PATH
359/230 .Electro-mechanical

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3 359/290 (0 OR, 3 XR)  
 Class 359 : OPTICS: SYSTEMS  
 359/237 OPTICAL MODULATOR  
 359/238 .Light wave temporal modulation (e.g.,  
 frequency, amplitude, etc.)  
 359/290 ..By changing physical characteristics (e.g.,  
 shape, size or contours) of an optical elem

ent

3 359/291 (2 OR, 1 XR)  
 Class 359 : OPTICS: SYSTEMS  
 359/237 OPTICAL MODULATOR  
 359/238 .Light wave temporal modulation (e.g.,  
 frequency, amplitude, etc.)  
 359/290 ..By changing physical characteristics (e.g.,  
 shape, size or contours) of an optical ele

ment

359/291 ...Shape or contour of light control surface  
 altered

3 430/22 (2 OR, 1 XR)  
 Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,  
 COMPOSITION, OR PRODUCT THEREOF  
 430/22 REGISTRATION OR LAYOUT PROCESS OTHER THAN COLO

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## PROOFING

3 438/458 (2 OR, 1 XR)  
 Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS  
 438/455 BONDING OF PLURAL SEMICONDUCTOR SUBSTRATES  
 438/458 .Subsequent separation into plural bodies  
 (e.g., delaminating, dicing, etc.)

3 438/459 (0 OR, 3 XR)  
 Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS  
 438/455 BONDING OF PLURAL SEMICONDUCTOR SUBSTRATES  
 438/459 .Thinning of semiconductor substrate

3 438/48 (0 OR, 3 XR)  
 Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS  
 438/48 MAKING DEVICE OR CIRCUIT RESPONSIVE TO  
 NONELECTRICAL SIGNAL

3 438/515 (3 OR, 0 XR)

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Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/510 INTRODUCTION OF CONDUCTIVITY MODIFYING DOPANT  
INTO SEMICONDUCTIVE MATERIAL

438/514 .Ion implantation of dopant into semiconductor  
region

438/515 ..Ionized molecules

3 438/706 (0 OR, 3 XR)  
Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/689 CHEMICAL ETCHING

438/706 .Vapor phase etching (i.e., dry etching)

3 438/712 (0 OR, 3 XR)  
Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/689 CHEMICAL ETCHING

438/706 .Vapor phase etching (i.e., dry etching)

438/707 ..Utilizing electromagnetic or wave energy

438/710 ...By creating electric field (e.g., plasma,  
glow discharge, etc.)

438/712 ....Reactive ion beam etching (i.e., RIBE)

3 438/739 (0 OR, 3 XR)  
Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/689 CHEMICAL ETCHING

438/706 .Vapor phase etching (i.e., dry etching)

438/735 ..Differential etching of semiconductor  
substrate

438/737 ...Substrate possessing multiple layers

438/738 ....Selectively etching substrate possessing  
multiple layers of differing etch characte

istics

438/739 .....Lateral etching of intermediate layer  
(i.e., undercutting)

3 445/24 (1 OR, 2 XR)  
Class 445 : ELECTRIC LAMP OR SPACE DISCHARGE COMPONENT OR  
DEVICE MANUFACTURING

445/1 PROCESS

445/23 .With assembly or disassembly

445/24 ..Display or gas panel making

2 29/596 (0 OR, 2 XR)  
Class 029 : METAL WORKING

29/592 METHOD OF MECHANICAL MANUFACTURE

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29/592.1 .Electrical device making

29/596 ..Dynamoelectric machine

2 29/598 (1 OR, 1 XR)

Class 029 : METAL WORKING

29/592 METHOD OF MECHANICAL MANUFACTURE

29/592.1 .Electrical device making

29/596 ..Dynamoelectric machine

29/598 ...Rotor

2 73/514.16 (2 OR, 0 XR)

Class 073 : MEASURING AND TESTING

73/488 SPEED, VELOCITY, OR ACCELERATION

73/514.01 .Acceleration determination utilizing inertial element

73/514.16 ..Specific type of electric sensor or specific type of magnetic sensor

2 73/514.32 (0 OR, 2 XR)

Class 073 : MEASURING AND TESTING

73/488 SPEED, VELOCITY, OR ACCELERATION

73/514.01 .Acceleration determination utilizing inertial element

73/514.16 ..Specific type of electric sensor or specific type of magnetic sensor

73/514.32 ...Capacitive sensor

2 73/654 (0 OR, 2 XR)

Class 073 : MEASURING AND TESTING

73/570 VIBRATION

73/649 .Sensing apparatus

73/652 ..With inertia element

73/654 ...With electrically controlled indicator

2 156/230 (0 OR, 2 XR)

Class 156 : ADHESIVE BONDING AND MISCELLANEOUS CHEMICAL MANUFACTURE

156/1 METHODS

156/60 .Surface bonding and/or assembly therefor

156/230 ..Direct contact transfer of adhered lamina from carrier to base

2 156/233 (0 OR, 2 XR)

Class 156 : ADHESIVE BONDING AND MISCELLANEOUS CHEMICAL MANUFACTURE

156/1 METHODS

156/60 .Surface bonding and/or assembly therefor

156/230 ..Direct contact transfer of adhered lamina



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from carrier to base

156/233 ...Metal foil lamina

2 156/241 (2 OR, 0 XR)  
Class 156 : ADHESIVE BONDING AND MISCELLANEOUS CHEMICAL  
MANUFACTURE  
156/1 METHODS  
156/60 .Surface bonding and/or assembly therefor  
156/230 ..Direct contact transfer of adhered lamina  
from carrier to base  
156/241 ...To base coated with adhesive

2 156/250 (0 OR, 2 XR)  
Class 156 : ADHESIVE BONDING AND MISCELLANEOUS CHEMICAL  
MANUFACTURE  
156/1 METHODS  
156/60 .Surface bonding and/or assembly therefor  
156/250 ..With cutting, punching, tearing or severing

2 156/256 (0 OR, 2 XR)  
Class 156 : ADHESIVE BONDING AND MISCELLANEOUS CHEMICAL  
MANUFACTURE  
156/1 METHODS  
156/60 .Surface bonding and/or assembly therefor  
156/250 ..With cutting, punching, tearing or severing  
156/256 ...Prior to assembly

2 156/344 (1 OR, 1 XR)  
Class 156 : ADHESIVE BONDING AND MISCELLANEOUS CHEMICAL  
MANUFACTURE  
156/1 METHODS  
156/344 .Delaminating, per se

2 204/192.32 (0 OR, 2 XR)  
Class 204 : CHEMISTRY: ELECTRICAL AND WAVE ENERGY  
204/192.1 .Coating, forming or etching by sputtering  
204/192.32 ..Sputter etching

2 204/192.37 (2 OR, 0 XR)  
Class 204 : CHEMISTRY: ELECTRICAL AND WAVE ENERGY  
204/192.1 .Coating, forming or etching by sputtering  
204/192.32 ..Sputter etching  
204/192.35 ...Etching specified material  
204/192.37 ....Silicon containing

2 204/298.32 (0 OR, 2 XR)

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Class 204 : CHEMISTRY: ELECTRICAL AND WAVE ENERGY  
 204/193 APPARATUS  
 204/298.01 .Coating, forming or etching by sputtering  
 204/298.31 ..Etching  
 204/298.32 ...Measuring, analyzing or testing

2 204/298.36 (0 OR, 2 XR)

Class 204 : CHEMISTRY: ELECTRICAL AND WAVE ENERGY  
 204/193 APPARATUS  
 204/298.01 .Coating, forming or etching by sputtering  
 204/298.31 ..Etching  
 204/298.36 ...Beam or directed flux etching (e.g., ion beam, etc.)

2 216/52 (0 OR, 2 XR)

Class 216 : ETCHING A SUBSTRATE: PROCESSES  
 216/52 MECHANICALLY SHAPING, DEFORMING, OR ABRADING O

F

SUBSTRATE

2 225/2 (0 OR, 2 XR)

Class 225 : SEVERING BY TEARING OR BREAKING  
 225/1 METHODS  
 225/2 .With preliminary weakening

2 244/130 (0 OR, 2 XR)

Class 244 : AERONAUTICS  
 244/117R AIRCRAFT STRUCTURE  
 244/129.1 .Details  
 244/130 ..Aerodynamic resistance reducing

2 244/204 (2 OR, 0 XR)

Class 244 : AERONAUTICS  
 244/34R AIRCRAFT SUSTENTATION  
 244/35R .Sustaining airfoils  
 244/198 ..With lift modification  
 244/201 ...Variable  
 244/204 ....By controlling boundary layer

2 250/492.21 (0 OR, 2 XR)

Class 250 : RADIANT ENERGY  
 250/492.1 IRRADIATION OF OBJECTS OR MATERIAL  
 250/492.2 .Irradiation of semiconductor devices  
 250/492.21 ..Ion bombardment

2 257/418 (0 OR, 2 XR)

Class 257 : ACTIVE SOLID-STATE DEVICES  
 257/414 RESPONSIVE TO NON-ELECTRICAL SIGNAL (E.G.,

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CHEMICAL, STRESS, LIGHT, OR MAGNETIC FIE

LD SENSORS)

257/415 .Physical deformation  
 257/417 ..Strain sensors  
 257/418 ...With means to concentrate stress

2 257/419 (1 OR, 1 XR)

Class 257 : ACTIVE SOLID-STATE DEVICES  
 257/414 RESPONSIVE TO NON-ELECTRICAL SIGNAL (E.G.,  
 CHEMICAL, STRESS, LIGHT, OR MAGNETIC FI

ELD SENSORS)

257/415 .Physical deformation  
 257/417 ..Strain sensors  
 257/418 ...With means to concentrate stress  
 257/419 ....With thinned central active portion of  
 semiconductor surrounded by thick insensiti

ve portion

(e.g., diaphragm type strain gauge)

2 257/420 (0 OR, 2 XR)

Class 257 : ACTIVE SOLID-STATE DEVICES  
 257/414 RESPONSIVE TO NON-ELECTRICAL SIGNAL (E.G.,  
 CHEMICAL, STRESS, LIGHT, OR MAGNETIC FIEL

D SENSORS)

257/415 .Physical deformation  
 257/420 ..Means to reduce sensitivity to physical  
 deformation

2 257/659 (0 OR, 2 XR)

Class 257 : ACTIVE SOLID-STATE DEVICES  
 257/659 WITH SHIELDING (E.G., ELECTRICAL OR MAGNETIC  
 SHIELDING, OR FROM ELECTROMAGNETIC RADIATIO

N OR CHARGE

PARTICLES)

2 257/737 (0 OR, 2 XR)

Class 257 : ACTIVE SOLID-STATE DEVICES  
 257/734 COMBINED WITH ELECTRICAL CONTACT OR LEAD  
 257/737 .Bump leads

2 310/268 (0 OR, 2 XR)

Class 310 : ELECTRICAL GENERATOR OR MOTOR STRUCTURE  
 310/10 DYNAMOELECTRIC  
 310/40R .Rotary  
 310/261 ..Rotor structure  
 310/264 ...Armatures  
 310/268 ....Disc

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2 315/111.41 (0 OR, 2 XR)  
Class 315 : ELECTRIC LAMP AND DISCHARGE DEVICES: SYSTEMS

315/111.01 DISCHARGE DEVICE LOAD WITH FLUENT MATERIAL  
SUPPLY TO THE DISCHARGE SPACE

315/111.21 .Plasma generating  
315/111.41 ..With magnetic field

2 315/111.71 (0 OR, 2 XR)  
Class 315 : ELECTRIC LAMP AND DISCHARGE DEVICES: SYSTEMS

315/111.01 - DISCHARGE DEVICE LOAD WITH FLUENT MATERIAL  
SUPPLY TO THE DISCHARGE SPACE

315/111.21 .Plasma generating  
315/111.41 ..With magnetic field  
315/111.71 ...Plasma containment

2 359/198 (1 OR, 1 XR)  
Class 359 : OPTICS: SYSTEMS

359/196 DEFLECTION USING A MOVING ELEMENT OR MEDIUM  
(OFFSETTING OR CHANGING AT LEAST A PORTIO  
N OF THE BEAM)

359/197 .Using a periodically moving element (periodic  
change of optically reflecting, refracting  
or diffracting  
element)

359/198 ..Particular mount or driver for element

2 359/223 (0 OR, 2 XR)  
Class 359 : OPTICS: SYSTEMS

359/196 DEFLECTION USING A MOVING ELEMENT OR MEDIUM  
(OFFSETTING OR CHANGING AT LEAST A PORTION  
OF THE BEAM)

359/223 .By moving a reflective element

2 361/233 (1 OR, 1 XR)  
Class 361 : ELECTRICITY: ELECTRICAL SYSTEMS AND DEVICES

361/230 ELECTRIC CHARGE GENERATING OR CONDUCTING MEANS  
(E.G., CHARGING OF GASES)

361/233 .Use of forces of electric charge or field

2 427/523 (0 OR, 2 XR)  
Class 427 : COATING PROCESSES

427/457 DIRECT APPLICATION OF ELECTRICAL, MAGNETIC,  
WAVE, OR PARTICULATE ENERGY

427/523 .Ion plating or implantation

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2 427/524 (0 OR, 2 XR)  
 Class 427 : COATING PROCESSES  
 427/457 DIRECT APPLICATION OF ELECTRICAL, MAGNETIC,  
 WAVE, OR PARTICULATE ENERGY  
 427/523 .Ion plating or implantation  
 427/524 ..With simultaneous sputter etching of  
 substrate

2 427/527 (0 OR, 2 XR)  
 Class 427 : COATING PROCESSES  
 427/457 DIRECT APPLICATION OF ELECTRICAL, MAGNETIC,  
 WAVE, OR PARTICULATE ENERGY  
 427/523 .Ion plating or implantation  
 427/527 ..Silicon present in substrate, plating, or  
 implanted layer

2 430/319 (0 OR, 2 XR)  
 Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,  
 COMPOSITION, OR PRODUCT THEREOF  
 430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF  
 RADIATION SENSITIVE MATERIAL, OR PRODUCIN

G NONPLANAR OR  
 PRINTING SURFACE - PROCESS, COMPOSITION,  
 OR PRODUCT

430/311 .Making electrical device  
 430/319 ..Named electrical device

2 430/5 (1 OR, 1 XR)  
 Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,  
 COMPOSITION, OR PRODUCT THEREOF  
 430/4 RADIATION MODIFYING PRODUCT OR PROCESS OF  
 MAKING  
 430/5 .Radiation mask

2 438/107 (1 OR, 1 XR)  
 Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS  
 438/106 PACKAGING (E.G., WITH MOUNTING, ENCAPSULATING,  
 ETC.) OR TREATMENT OF PACKAGED SEMICONDUCT

OR  
 438/107 .Assembly of plural semiconductive substrates  
 each possessing electrical device

2 438/120 (2 OR, 0 XR)  
 Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS  
 438/106 PACKAGING (E.G., WITH MOUNTING, ENCAPSULATING,  
 ETC.) OR TREATMENT OF PACKAGED SEMICONDUCT

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OR

438/120 .With vibration step

2 438/127 (0 OR, 2 XR)

Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/106 PACKAGING (E.G., WITH MOUNTING, ENCAPSULATING,  
ETC.) OR TREATMENT OF PACKAGED SEMICONDUCT

OR

438/127 .Encapsulating

2 438/26 (0 OR, 2 XR)

Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/22 MAKING DEVICE OR CIRCUIT EMISSIVE OF  
NONELECTRICAL SIGNAL

438/26 .Packaging (e.g., with mounting, encapsulating

,

etc.) or treatment of packaged semiconducto

r

2 438/28 (2 OR, 0 XR)

Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/22 MAKING DEVICE OR CIRCUIT EMISSIVE OF  
NONELECTRICAL SIGNAL

438/26 .Packaging (e.g., with mounting, encapsulating

,

etc.) or treatment of packaged semiconduct

or

438/28 ..Plural emissive devices

2 438/34 (0 OR, 2 XR)

Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/22 MAKING DEVICE OR CIRCUIT EMISSIVE OF  
NONELECTRICAL SIGNAL

438/34 .Making emissive array

2 438/406 (1 OR, 1 XR)

Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/400 FORMATION OF ELECTRICALLY ISOLATED LATERAL  
SEMICONDUCTIVE STRUCTURE

438/404 .Total dielectric isolation

438/406 ..Bonding of plural semiconductive substrates

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2 438/456 (0 OR, 2 XR)  
Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/455 BONDING OF PLURAL SEMICONDUCTOR SUBSTRATES  
438/456 .Having enclosed cavity

2 438/457 (0 OR, 2 XR)  
Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/455 BONDING OF PLURAL SEMICONDUCTOR SUBSTRATES  
438/457 .Warping of semiconductor substrate

2 438/464 (0 OR, 2 XR)  
Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/460 SEMICONDUCTOR SUBSTRATE DICING  
438/464 .With attachment to temporary support or  
carrier

2 438/51 (0 OR, 2 XR)  
Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/48 MAKING DEVICE OR CIRCUIT RESPONSIVE TO  
NONELECTRICAL SIGNAL  
438/50 .Physical stress responsive  
438/51 ..Packaging (e.g., with mounting,  
encapsulating, etc.) or treatment of packa  
ged semiconductor

2 438/692 (0 OR, 2 XR)  
Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/689 CHEMICAL ETCHING  
438/690 .Combined with the removal of material by  
nonchemical means (e.g., ablating, abradi  
ng, etc.)

438/691 ..Combined mechanical and chemical material  
removal  
438/692 ...Simultaneous (e.g., chemical-mechanical  
polishing, etc.)

2 438/745 (1 OR, 1 XR)  
Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/689 CHEMICAL ETCHING  
438/745 .Liquid phase etching

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2 438/753 (0 OR, 2 XR)  
 Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/689 CHEMICAL ETCHING  
 438/745 .Liquid phase etching  
 438/753 ..Silicon

2 438/800 (0 OR, 2 XR)  
 Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/800 MISCELLANEOUS

2 438/933 (0 OR, 2 XR)  
 Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/933 GERMANIUM OR SILICON OR GE-SI ON III-V

2 445/50 (0 OR, 2 XR)  
 Class 445 : ELECTRIC LAMP OR SPACE DISCHARGE COMPONENT OR  
 DEVICE MANUFACTURING

445/1 PROCESS  
 445/46 .Electrode making  
 445/49 ..Electrode shaping  
 445/50 ...Emissive type

2 451/388 (1 OR, 1 XR)  
 Class 451 : ABRADING

451/364 WORK HOLDER  
 451/388 .Vacuum



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Most Frequently Occurring Classifications of Patents Returned  
From A Search of 09681304 on March 13, 2002

Original Classifications

10	310/307
4	216/2
4	438/50
3	148/33.2
3	257/415
3	310/40MM
3	438/460
3	438/515
3	438/52
2	73/514.16
2	73/514.21
2	118/723E
2	118/723IR
2	156/241
2	156/345
2	200/181
2	204/192.37
2	244/204
2	257/417
2	271/194
2	310/309
2	359/291
2	430/22
2	438/120
2	438/28
2	438/458

Cross-Reference Classifications

9	438/52
7	257/417
6	438/50
5	216/2
5	438/455
4	73/514.36
4	118/728
4	310/40MM
3	118/723I
3	118/723MP
3	118/733
3	156/247
3	156/267
3	156/345
3	216/67

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3 257/254  
3 257/415  
3 271/195  
3 310/306  
3 310/DIG 6  
3 359/230  
3 359/290  
3 438/459  
3 438/48  
3 438/526  
3 438/53  
3 438/706  
3 438/712  
3 438/739  
2 29/596  
2 73/514.32  
2 73/654  
2 118/723IR  
2 156/230  
2 156/233  
2 156/250  
2 156/256  
2 204/192.32  
2 204/298.15  
2 204/298.32  
2 204/298.36  
2 216/52  
2 225/2  
2 244/130  
2 250/492.21  
2 257/418  
2 257/420  
2 257/659  
2 257/737  
2 310/268  
2 315/111.41  
2 315/111.71  
2 359/223  
2 359/224  
2 427/523  
2 427/524  
2 427/527  
2 430/319  
2 438/127  
2 438/26  
2 438/34  
2 438/456  
2 438/457

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2 438/464  
2 438/51  
2 438/692  
2 438/753  
2 438/800  
2 438/933  
2 445/24  
2 445/50

Combined Classifications

12 438/52  
11 310/307  
10 438/50  
9 216/2  
9 257/417  
7 310/40MM  
6 257/415  
6 438/455  
5 156/345  
4 73/514.36  
4 118/723IR  
4 118/728  
4 257/254  
4 310/306  
4 438/460  
4 438/526  
4 438/53  
3 73/514.21  
3 118/723E  
3 118/723I  
3 118/723MP  
3 118/733  
3 148/33.2  
3 156/247  
3 156/267  
3 200/181  
3 204/298.15  
3 216/67  
3 271/194  
3 271/195  
3 310/309  
3 310/DIG 6  
3 359/224  
3 359/230  
3 359/290  
3 359/291  
3 430/22  
3 438/458

3 438/459  
3 438/48  
3 438/515  
3 438/706  
3 438/712  
3 438/739  
3 445/24  
2 29/596  
2 29/598  
2 73/514.16  
2 73/514.32  
2 73/654  
2 156/230  
2 156/233  
2 156/241  
2 156/250  
2 156/256  
2 156/344  
2 204/192.32  
2 204/192.37  
2 204/298.32  
2 204/298.36  
2 216/52  
2 225/2  
2 244/130  
2 244/204  
2 250/492.21  
2 257/418  
2 257/419  
2 257/420  
2 257/659  
2 257/737  
2 310/268  
2 315/111.41  
2 315/111.71  
2 359/198  
2 359/223  
2 361/233  
2 427/523  
2 427/524  
2 427/527  
2 430/319  
2 430/5  
2 438/107  
2 438/120  
2 438/127  
2 438/26  
2 438/28

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2 438/34  
2 438/406  
2 438/456  
2 438/457  
2 438/464  
2 438/51  
2 438/692  
2 438/745  
2 438/753  
2 438/800  
2 438/933  
2 445/50  
2 451/388

09681304\_QUAL

6335224 95  
6287765 86  
6124663 84  
5389182 81  
5905007 80  
6071819 80  
5923995 76  
6188814 76  
5647044 76  
5710065 73  
5979728 73  
6116756 72  
6180428 72  
5637539 71  
5912094 71  
5955817 71  
5994816 71  
6023121 71  
6078103 71  
6096149 71  
6114794 71  
6173650 71  
6180536 71  
6239473 71  
6310018 71  
6321654 71  
6342430 71  
5955659 70  
6142358 70  
5761350 70  
6008776 70  
6045712 70  
6072686 70  
6225145 70  
6225145 70  
5445559 69  
5605489 69  
5938952 69  
6140144 69  
6303986 69  
5910856 69  
5914553 69  
6057520 69  
6127812 69  
6211598 69  
6211598 69  
6229683 69  
6236491 69

09681304\_QUAL

5837935 68  
5929497 68  
6060336 68  
6109222 68  
6140646 68  
6210988 65  
6210988 65  
5412265 65  
5592037 65  
5685062 65  
6054335 65  
6167809 65  
5331236 65  
5378330 65  
5426070 65  
5628917 65  
5642015 65  
5645684 65  
5660680 65  
5717631 65  
5726480 65  
5755408 65  
5783340 65  
5786621 65  
5804084 65  
5843832 65  
5874675 65  
5903099 65  
5907768 65  
5909078 65  
5914507 65  
5917226 65  
5919364 65  
5941481 65  
5962949 65  
5976994 65  
5985742 65  
5990473 65  
5994207 65  
5994638 65  
6000280 65  
6010579 65  
6013567 65  
6013563 65  
6015599 65  
6025767 65  
6027112 65  
6028343 65

09681304\_QUAL

6033974 65  
6039316 65  
6040935 65  
6048411 65  
6051073 65  
6058778 65  
6058778 65  
6065864 65  
6113735 65  
6114188 65  
6119052 65  
6116863 65  
6120660 65  
6123985 65  
6134042 65  
6137206 65  
6136243 65  
6143583 65  
6143997 65  
6146979 65  
6146227 65  
6149190 65  
6153524 65  
6155490 65  
6155909 65  
6156652 65  
6159824 65  
6159825 65  
6162705 65  
6166478 65  
6169321 65  
6170332 65  
6171879 65  
6171965 65  
6184111 65  
6186091 65  
6187110 65  
6193501 65  
6199575 65  
6199874 65  
6204151 65  
6207005 65  
6210514 65  
6213050 65  
6217724 65  
6218205 65  
6218209 65  
6218762 65



09681304\_QUAL

6220096 65  
6210514 65  
6213050 65  
6217724 65  
6218205 65  
6218209 65